2025년 2월 12일(수)-14일(금) | 강원도 하이원리조트

Future Normal in Semiconductor

2025-02-13(목), 10:55-12:40
좌장: 추후업데이트 예정

B. Patterning (Lithography & Etch Technology) 분과

[TL2-B] Lithography

초청 TL2-B-1 10:55-11:25	**Challenges and Development Status of Next Generation EUV Patterning Materials** Chawon Koh Yonsei University
TL2-B-2 11:25-11:40	**Memory Device의 High NA EUV Stitching 고려사항** Dae-Jin Park, Da-Jeong Kang, Jeon-Kyu Lee, and Sung-Woo Ko SK Hynix
초청 TL2-B-3 11:40-12:10	**Enhancing the Patterning Performance of Metal Oxide Resists for High NA EUV Lithography** Yejin Ku[1], Gayoung Kim[1], Jin-Kyun Lee[1], Jiho Kim[2], Sangsul Lee[2], Seohyeon Lee[3], Byung Jun Jung[3], Chawon Koh[4], Tsunehiro Nishi[5], and Hyun-Woo Kim[5] [1]Inha University ,[2]Pohang Accelerator Laboratory, [3]Korea University of Seoul, [4]Yonsei University, [5]Samsung Electronics Co., Ltd.
TL2-B-4 12:10-12:25	**IM-HAPPY: AI-Based Polymer Resist Design for Enhanced Patterning Performance** Jihun Ahn[1], Hyunseok Kim[1], Vikram Thapar[1], Gabriella Pasya Irianti[1] and Su-Mi Hur[1,2] [1]Department of Polymer Engineering, Graduate School, Chonnam National University, [2]School of Polymer Science and Engineering, Chonnam National University
TL2-B-5 12:25-12:40	**High-NA EUV 마스크 적용을 위한 차세대 흡수 소재 패터닝 성능 개선 연구** 김연수[1,2], 정동민[1,2], 이승호[1,2], 이태호[2], 안진호[1,2] [1]한양대학교 신소재공학과, [2]Center for Hyperscale, Hyperfunction, Heterogeneous Integration Pioneering Semiconductor Technology